

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Examiner:

DT09 Rec'd PCT/PTO 01 SEP 2004
Unassigned

Hyosang KANG

Serial No.: Unassigned

Art Unit: Unassigned

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Title: METHOD FOR DRY ETCHING A SEMICONDUCTOR WAFER

Mail Stop PCT
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

**INFORMATION DISCLOSURE STATEMENT PURSUANT TO
37 C.F.R. §§1.97-1.98**

Sir:

In accordance with the duty of disclosure under 37 CFR §1.56 and pursuant to 37 CFR §§1.97-1.98, Applicants hereby notify the U.S. Patent and Trademark Office of the references listed on the attached Form PTO-1449. One copy of each cited reference, except the U.S. references, is submitted herewith.

The present Information Disclosure Statement is being filed within three months of the filing date of the above-referenced application. Accordingly, no certification or fee is required.

The submission of the listed documents is not intended as an admission that any such document constitutes prior art against the claims of the present application. Applicant reserves the right to dispute any of the listed documents as prior art during examination. Furthermore, Applicant does not waive any right to take any action that would be appropriate to antedate or otherwise remove any listed document as a competent reference against the claims of the present application. The submission of this Information Disclosure Statement is not to be construed as a representation that a search has been made or that no other material information may exist.

The Examiner is requested to initial the enclosed Form PTO-1449 and return a copy thereof to the undersigned.

10/506478
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If for any reason an insufficient fee has been paid, please charge the insufficiency to Deposit Account No. 05-0150.

Date: 9-1-2004

Respectfully submitted,
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